



## **III - V Leading Supplier**

#### **OMMIC at a Glance**

OMMIC, based near Paris in France, is a leading supplier of Epitaxy, Foundry Services and MMICs based around the most advanced III-V processes.

Formerly Phillips Semiconductor, OMMIC is exploiting more than 40 years background in III-V Materials, Design and Processing. Thanks to its innovative solutions, OMMIC enables its customers to be leaders in a more and more demanding market place.

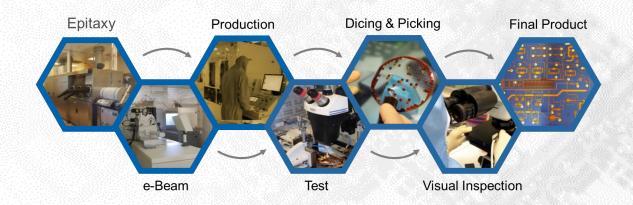
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OMMIC operates in a highly competitive global market and must be competitive and responsive.

OMMIC has been ISO 9001 certified since 1994 and ISO 14001 since 2002.

This sustainable commitment is fully supported by its quality management system.



OMMIC is supplying MMIC, Foundry Services and Epitaxial Wafers based on III-V (GaN GaAs and InP) materials. With its advanced technology, OMMIC has proven itself as a leader in its field, providing its customers with cutting edge performance in the Telecommunication, Space and Defense markets.





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## **New Production Line**



## World's 1st 6" GaN/Si Line in Production



The new 6-inch GaN production line will largely boost OMMIC's production capability by 4 times. Combined with improved production yield and increased work shifts, it is estimated to have 7 times of present production capabilities.



Thanks to improved process automation and 5 work shifts in 2019, lead time will be reduced to 7 weeks

With this new production line, OMMIC has set itself three goals for the comming years :



#### Leader in GaN

OMMIC to become the first and unique foundry in Europe for mmW GaN technology on 6-inch wafers.

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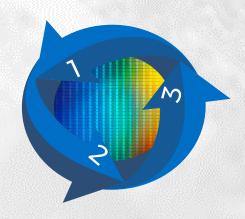
#### Top 3

OMMIC to become top 3 foundry in the world for GaAs and GaN technology.



#### € 100 000 000

OMMIC to reach 100 million euros sales in the year of 2020.



## Strategy & Roadmap

OMMIC strategy is articulated around GaN technology. With its wide bandgap and high electron mobility, GaN is a perfect candidate for emerging applications.

#### Our strategy includes



#### Full Replacement of GaAs Solutions

OMMIC plans to fully replace its GaAs pHEMT solutions by its state-of-the-art GaN/Si technology, offering the best III–V RF solutions, complementary to Silicon RF solutions.



#### New Cellular Telecom Market

OMMIC aims to enter cellular infrastructure market, especially 5G market with its cuttingedge GaN/Si technology, best suited for the 5G mmWave application.



#### High-End Space Market

OMMIC continues to serve high-end high value-added space market, by taking advantage of its avant-garde Hi-Reliability process for consumer market.



#### High-End Defense Market

MMIC continues to serve high-end high value-added military market, by taking advantage it its high-performance process for consumer market.

DOIGH GaN/Si process is already available for OMMIC customer through open foundry service

DO06GH GaN/SiC 60 nm process PDK is already available for download

f<sub>max</sub> = 250GHz, f<sub>t</sub>: 170 GHz, Gate length: 60nm, I<sub>max</sub> = 1,1 A/mm, Gm = 700 mS/mm, P<sub>max</sub> = 1 W/mm @ 94 GHz, V<sub>bdg</sub> > 30V, NF<sub>min</sub> = 1 dB @ 50 GHz

DO04GH GaN/SiC 40 nm process is still in development and will be available in 2020

State-of-the-art and unique 40 nm

process for GaN technology

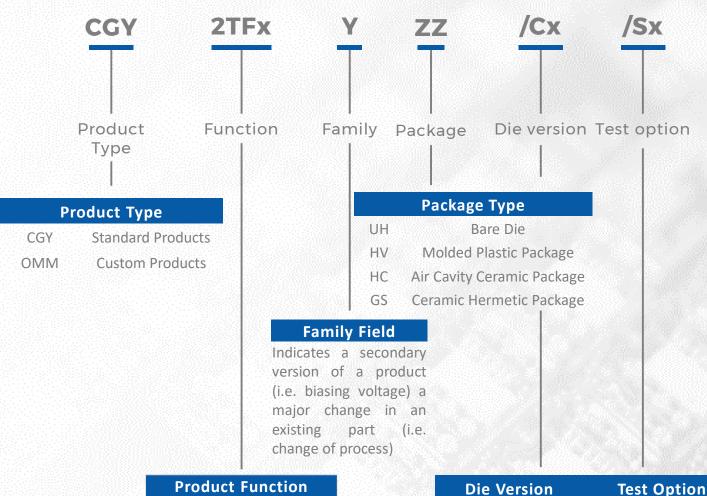
D01GH (Si)
110 GHz Ft
3,3 W/mm @ 30 GHz

D006GH (SiC)
150 GHz Ft
2 W/mm @ 94 GHz

D004GH (SiC)
210 GHz Ft
0,8 W/mm @ 140 GHz

## **Part Numbering**

Part designation at OMMIC are following defined rules; each field is related to the following items



#### **Product Function**

A four digit number from CGY2100 to 2999 (standard products) or OMM9200 to 9999 (custom products)

		gauru.			
Т	Function Digit	F	Frequency	Digit	
0	Not allowed	0	0-4	GHz	
1	Legacy notation	1	4-8	GHz	
2	LNA	2	8-12	GHz	
3	Control Functions	3	12-18	GHz	
4	Frequency conversion	4	18-26.5	GHz	
5	Wide band amplifier	5	26.5-40	GHz	
6	PA	6	40-75	GHz	
7	Amplifier (General)	7	75-110	GHz	
8	Other functions	8	110-400	GHz	
9	Special	9	6-18	GHz	

#### Die Version

The x number of this field is incremented for each version or redesign of the die

## The x number of this

field is incremented for each customer specific test applied on a standard product. The F letter indicates a flight model device

#### **Part Number Example**

Standard Product

Version A

**Design Version 1** 

CGY 2175 A HV /C1 /S1

Part Number

Plastic OFN

Special Test for Customer 1

# MMIC Product Selector Guide

## **Advanced mmW MMIC Solutions**

Innovative GaN Products (15 - 50 GHz)

Low Noise Amplifiers (0,5 - 120 GHz)

Power Amplifiers (0,5 - 46 GHz)

Wideband Amplifiers (DC - 54 GHz)

Digital Attenuator & Phase Shifters (5 - 35 GHz)

Corechips & Control Functions (5 - 35 GHz)



## **D01GH GaN/Si**

#### **Main Features**



 $f_{max}$ : 160 GHz  $f_{+}$ : 110 GHz

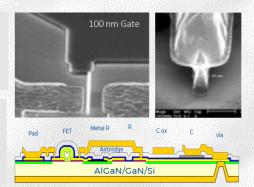
Gate length: 100 nm

 $V_{bgd}:40 V$ 

PRELIMINARY

PW @ 30 GHz: 3,5W/mm

PAE: 48%



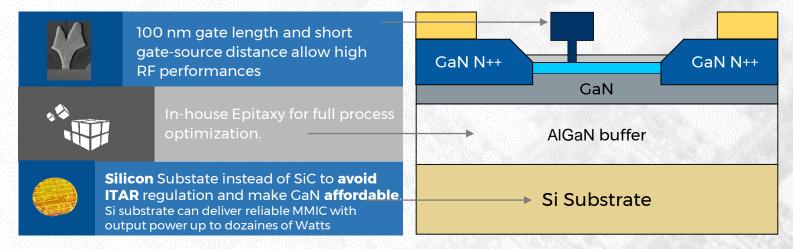


**ON-WAFER** 

**MEASUREMENTS** 

- High Linearity Mixers
- High frequency PA 15 GHz to 50 GHz
- Instrumentation wide band amplifier DC 50 GHz
- Robust LNA (< 40 GHz): up to 35dBm Pin in CW

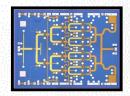
#### **OMMIC's GaN specificities**

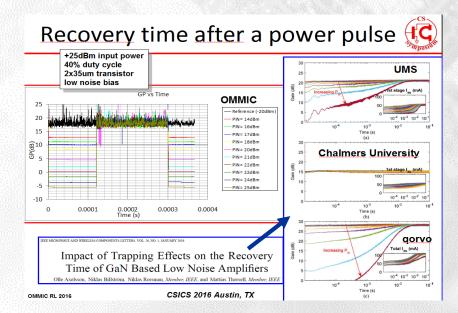


#### The only GaN Process in Production Having no Memory Effect

OMMIC's GaN has been engineered to reduce as much as possible traps in its process. This is why, unlike post process in production, OMMIC's DOIGH has few-to-no measurable memory effect.

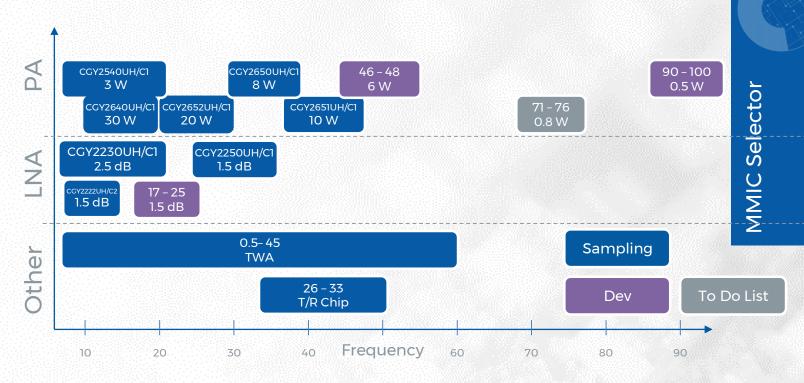
With D01GH, optimized digital predistortion technique can be used as much as complex modulation.





## **Innovative GaN Products Portfolio**

GaN products are being actively developed for emmerging applications; they are processed using D01GH GaN/Si technology which is 100 % european sourced and ITAR regulation free.

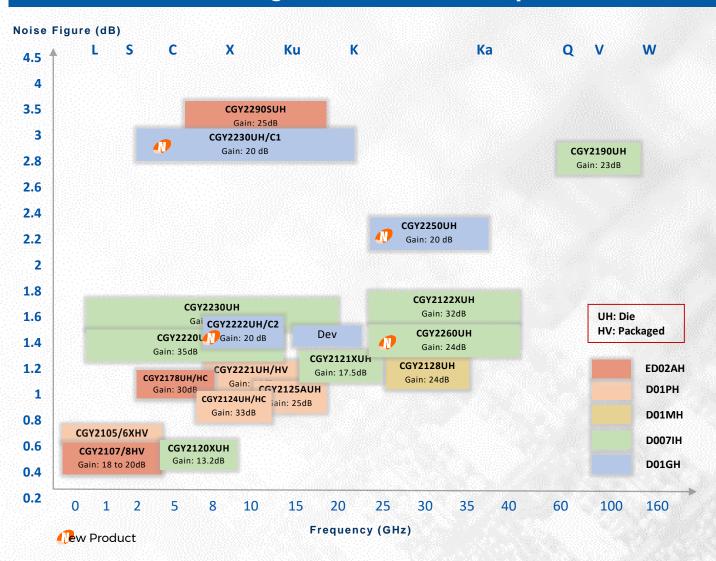


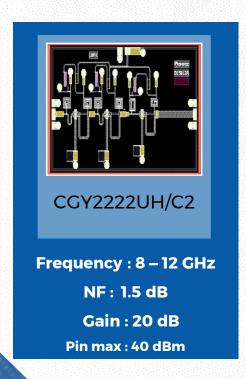
GaN LNA have been designed so that maximum input power is higher than 40 dBm. This is handy because, in most settings, no limitor is needed in front of the LNA

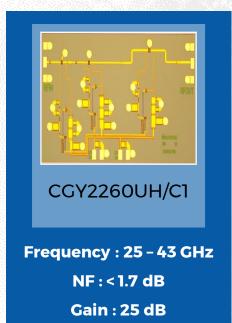
	Part number	Frequency (GHz)	Gain (dB)	NF (dB) OF	P1dB (dBm)	Bias Volta (V)	ge Bias Cu (m.	Pai	ckage	Status
Z Z Z	CGY2230UH/C1	2 – 20	17	2.5	22	8	15	5	Die	Sampling
2	CGY2222UH/C2	8 – 12	20	1.5	20	8	15	5	Die	Sampling
	CGY2250UH/C1	26 – 34	20	1.6	27	8.5	90	י	Die	Sampling
	Part number	Frequency (GHz)	Gain (dB)	Saturated Power (dBm	Compre n) Point P1d		as Voltage (V)	Bias Current (A)	Package	Status
	CGY2540UH/C1	0.5 – 20	22	35	100		12	0.7	Die	Sampling
×	CGY2640UH/C1	15 – 18	25	45	40	)	12	1	Die	Sampling
	CGY2650UH/C1	30 – 33.5	22	39	28.	5	12	0.7	Die	Sampling
	CGY2652UH/C1	27 – 31	20	43	41	L	12	0.46	Die	Sampling
	CGY2651UH/C1	37 – 43	18	40	38	3	12	0.84	Die	Sampling
TWA	Part number	Frequency (GHz)	Gain (dB)	Saturated Power (W)	Compre Point P1d		as Voltage (V)	Bias Current (mA)	Package	Status
F	CGY2550UH/C1	0.6 – 40	16	2	19 19	)	18	91	Die	Production
T/R	Part number	Frequency (GHz)	Gain (dB)	Output Pow (dBm)	er Noise Figu	ure (dB) Bi	as Voltage (V)	Bias Current (A)	Package	Status
F	CGY2750UH/C1	26 – 34	20	35	3		12	0.45	Die	Sampling

## **Low Noise Amplifiers Portfolio**

#### **Performance Figure for Low Noise Amplifiers MMIC**









## **Low Noise Amplifiers Portfolio**

OMMIC Portfolio of MMICs, includes LNA from 500 MHz to 160 GHz for application such as Telecommunication, Passive imaging, Radars and Space.

LNA are manufactured using GaAs technology (ED02AH, D01PH, D01MH) that have been Space qualified by ESA, or innovating technology: GaAs mHEMT (D007IH) for lower noises & higher frequencies or GaN HEMT (D01GH) for robust LNA.

### **Performance Table for Low Noise Amplifiers MMIC**

LNA written in blue are manufactured using GaN technology. They are therefore very robust an can handle more than 32 dBm input power in CW (>40 dBm in pulse)

Part number	Frequency (GHz)	Gain (dB)	NF (dB)	OP1dB (dBm)	Bias Voltage (V)	Bias Current (mA)	Package	Status
CGY2105XHV	0.5 – 4	19	0.42	35	5	2 x 50	QFN 4x4	Production
CGY2106XHV	0.1 – 3	19	0.45	35	5	2 x 50	QFN 4x4	Production
CGY2108HV	0.5 – 6	22	0.5	36	5	2 x 50	QFN 4x4	Production
CGY2107UH	0.5 – 6	24	0.6	34	5	2 x 50	QFN 4x4	Production
CGY2108GS	0.5 – 6	21	0.6	36	5	2 x 50	Flight Model	Production
CGY2120XUH/C1	5 – 7	13	0.5	12	1	50	Die	Production
CGY2178HV/C1	5 – 6	30	1	15	3	40	QFN	Production
CGY2178UH/C1	5 – 6	30	1	15	3	40	Die	Production
CGY2222UH/C2	8 – 12	20	1.5	20	8	155	Die	Sampling
CGY2124UH/C1	8 – 12	33	1.1	11	5	55	Die	Production
CGY2220UH/C1	1 – 12	35	1.3	12	1.5	52	Die	Production
CGY2221UH/C1	7.5 – 13	17	1.6	17	5	82	Die	Production
CGY2221HV/C1	7.5 – 13	17	1.7	17	5	82	QFN	Sampling
CGY2125UH/C1	13 – 15	25	1	8	3.3	20	Die	Production
CGY2230UH/C1	1 – 18	35	1.5	12	1.5	50	Die	Production
CGY2290SUH/C1	6 – 18	9	3.3	13	5	30	Die	Production
CGY2230UH/C1	2 – 20	17	2.5	22	8	155	Die	Sampling
CGY2121XUH/C2	18 – 26	18	1.5	5	0.8	60	Die	Production
CGY2250UH/C1	26 – 34	20	1.6	27	8.5	90	Die	Sampling
CGY2128UH/C2	24 – 34	24	1.3	11	3.5	47	Die	Production
CGY2122XUH/C2	25 – 43	32	1.5	1	1.1	30	Die	Production
CGY2260UH/C1	25 – 43	24	1.5	8	1.5	50	Die	Sampling
CGY2190UH/C2	75 – 110	23	3	1	1	33	Die	Production

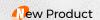
## **Power & Wideband Amplifiers Portfolio**

OMMIC Portfolio of MMICs, includes Amplifiers from DC to 46 GHz for civil application such as Telecommunication, Instrumentation, Radars but also for Satcom and military applications.

LNA are manufactured using GaAs technology (EDO2AH, DO1PH, DO1MH) that have been Space qualified by ESA, or innovating technology: GaAs mHEMT (DO07IH) for lower noises & higher frequencies or GaN HEMT (DO1GH) for robust LNA.

#### **Performance Table for (Power) Amplifiers MMIC**

OMMIC Power Amplifiers are dedicated to application such as Radar, telecommunication and instrumentation.



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	Part number	Frequency (GHz)	Gain (dB)	Saturated Power (dBm)	Compression Point P1dB (dBm)	Bias Voltage (V)	Bias Current (A)	Package	Status
•	CGY2540UH/C1	0.5 – 20	22	35		12	0.7	Die	Sampling
	CGY2620UH/C1	8_ 11	25	42	41	9	3.25	Die	Sampling
Ø	CGY2640UH/C1	15 – 18	25	45	40	12	1	Die	Sampling
	CGY2134UH/C1	18 – 23	23	23	22	4.5	0.3	Die	Production
	CGY2135UH/C1	18 – 23	25	33	32.3	4	1.2	Die	Production
0	CGY2652UH/C1	27 – 31	20	43	41	12	0.46	Die	Sampling
1	CGY2651UH/C1	37 – 43	18	40	38	12	0.84	Die	Sampling
	CGY2650UH/C1	30 – 33.5	22	39	28.5	12	0.7	Die	Production

The MMICs use gold bonding pads and backside metallization and are fully protected with Silicon Nitride passivation to get the highest level of reliability. **D01PH** technology has been evaluated for Space applications and is on the European Preferred Parts List of the European Space Agency.

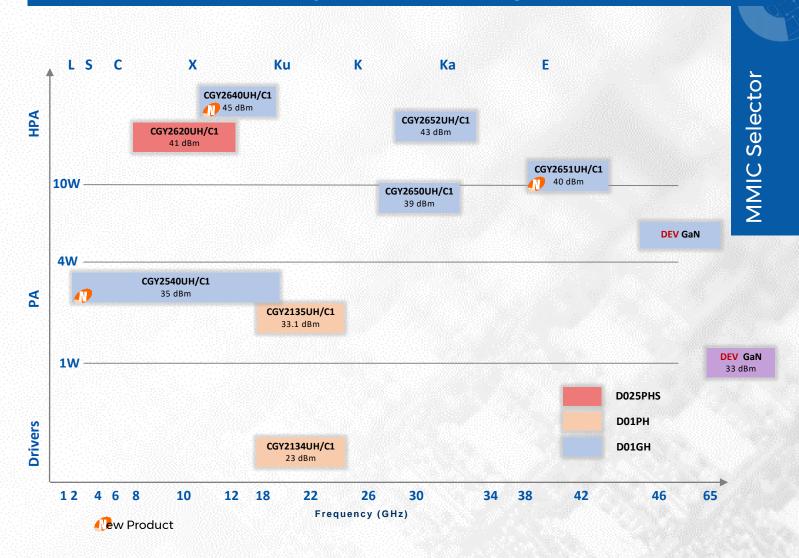
Wideband amplifiers are manufactured using OMMIC 130nm gate length PHEMT Technology **D01PH** or 130nm MHEMT Technology **D01MH**.

OMMIC Wideband Amplifiers are dedicated to application such as Instrumentation, Electronic warfare, 43 Gb/s OC-768 EAM Driver

	Part number	Frequency (GHz)	Gain (dB)	Saturated Power (W)	Compression Point P1dB (dBm)	Bias Voltage (V)	Bias Current (mA)	Package	Status
	CGY2141UH/C1	DC - 46	16	0.2	21	5	195	Die	Production
	CGY2144UH/C2	DC - 54	13	0.05	15	5	100	Die	Production
	CGY2145UH/C1	0.5 – 45	13	0.1	18	5	85	Die	Production
Ø	CGY2550UH/C1	0.6 - 40	16	1	19	18	91	Die	Sampling
	CGY2160UH/C1	1.5 – 47	15	0.08	17	5	103	Die	Production

## **Power & Wideband Amplifiers Portfolio**





## **Performance Figure for Wideband Amplifiers MMIC**



## **Control Function Advantages**



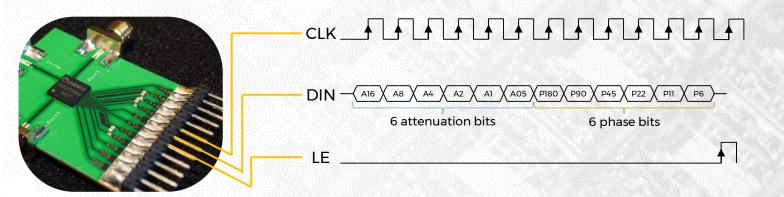
OMMIC Portfolio includes Corechip and control functions.

Corechips are based on the integration in a single die of Digital Phase Shifters, Digital Attenuators, LNA, MPA and Switches for phased array antenna applications. Phases and attenuation states are controlled through a Serial to Parallel interface on the die (SIPO) built with OMMIC's E/D technology,

**OMMIC SIPO stands for Serial Input Parallel Output.** 

With the SIPO, the number of bonding is greatly reduced and only three of them are needed to control a corechip.

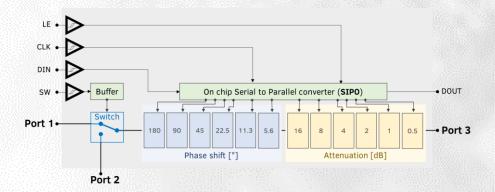
#### Example: CGY2175AHV/C1 (6-bit packaged C-band corechip)





Each phase and attenuation states are loaded in the shift register (at a clock (CLK) rate up to 250 MHz), then phase and attenuation configuration are changed after latch enable (LE) signal.

CGY2175AHV/C1 Block Diagram



## **Control Functions Portfolio**

#### **Performance Table for Digital Phase-Shifter Functions**

Phase shifter, Attenuators, LNA and MPA integrated into a single chip controlled through Serial CMOS TTL compatible access

Part number	Frequency (GHz)	Resolution (bits)	Topology	Ctrl Range (dB/°)	RMS Atten/Phase Error (dB/°)	Ctrl Interface (V)	Package	Status
CGY2175AUH/C1	4.5 – 6.5	6	3 ports	31.5 / 360	0.20 / 1.3	0/+5	Die	Production
CGY2175AHV/C1	4.5 – 6.5	6	3 ports	31.5 / 360	0.25 / 1.3	0/+5	Die	Production
CGY2170YUH/C1	8 – 12	6	3 ports	31.5 / 360	0.40 / 3.0	0/+3	Die	Production
CGY2170YHV/C1	8 – 12	6	3 ports	31.5 / 360	0.40 / 3.0	0/+3	QFN	Production
CGY2170XUH/C2	8 – 12	6	4 ports	31.5 / 360	0.30 / 3.0	0/+3	Die	Production
CGY2170XHV/C2	8 – 12	6	4 ports	31.5 / 360	0.35 / 3.0	0/+3	QFN	Production
CGY2350UH/C1	34 – 36	5	3 ports	31.5 / 360	0.35 / 3.0	0/+3	Die	Production
CGY2351UH/C1	26.5 – 30.5	6	2 ports	31.5 / 360	0.50 / 4.0	0/+5	Die	Production

Phase shifter + LNA integrated in one die for internet over satellites Rx phased array antenna application

Part number	Frequency (GHz)	Resolution (bits)	Topology	Gain / Noise (dB)	RMS Phase E (°)	rror Ctrl Interface (V)	Package	Status
CGY2179UH	10.7 – 12.5	4	2 ports	12 / 2	7.00	0/+5	Die	Production
CGY2179HV	10.7 – 12.8	4	2 ports	12 / 2	7.00	0/+5	QFN	Production

#### **Performance Table True-Time Delay Functions**

Part number	Frequency (GHz)	Resolution (bits)	Min Delay (ps)	Full Delay (ps)	Insertion Loss (dB)	Ctrl Interface (V)	Package	Status
CGY2393SUH/C1	6 – 18	5	10.00	310	6.00	0 / +4	Die	Production
CGY2394SUH/C1	6 – 18	1	330.00	310	6.00	0 / +4	Die	Production

#### **Performance Table for Digital Phase-Shifter Functions**

Part number	Frequency (GHz)	Resolution (bits)	Insertion Loss (dB)	Phase Range (°)	RMS Phase Erro (°)	Or Ctrl Interface (V)	Package	Status
CGY2177AUH/C1	4.8 - 6.8	6	5.00	360	2.00	0/+5	Die	Production
CGY2173UH/C2	6 – 18	6	13.00	360	4.00	0/-3	Die	Production
CGY2172XAUH/C1	8 – 12	6	8.00	360	2.00	0/-3	Die	Production
CGY2172XBUH/C1	8 – 12	6	8.00	360	2.00	0/+5	Die	Production
CGY2392SUH/C1	6 – 18	6	10.80	360	1.70	0/+5	Die	Production
CGY2392SHV/C1	6 – 18	6	10.80	360	1.90	0/+5	QFN	Production
CGY2174UH/C1	13 – 16	6	8.00	360	6.00	0/-3	Die	Production

#### **Performance Table for Digital Attenuators Functions**

Part number	Frequency (GHz)	Resolution (bits)	Insertion Loss (dB)	Atten Range (dB)	RMS Atten Eri (dB)	ror Ctrl Interface (V)	Package	Status
CGY2176UH/C1	4.8 - 6.8	6	5.60	32	0.20	0/+5	Die	Production
CGY2171XBUH/C1	1 – 12	6	5.00	32	0.25	0/+3	Die	Production
CGY2390SUH/C1	8 – 12	6	4.00	35	0.20	0/+5	Die	Production
CGY2169UH/C1	8 – 12	6	4.00	24	0.40	0 / -3	Die	Production
CGY2191SUH/C1	6 – 18	6	4.00	32	0.20	0/+5	Die	Production

## **Miscellaneous Portfolio**

OMMIC Portfolio of MMICs, includes up and down, passive and active converters, SPDT switches and diodes.

#### **Performance Table for Mixers**

Mixers are manufactured using OMMIC's GaAs 180 nm E/D PHEMT (ED02AH) and 70 nm MHEMT (D007IH) technologies. They generally feature high isolation and can be used for application such as radar, telecommunication, instrumentation and GPS system.

Part number	RF frequency (GHz)	LO frequency (GHz)	IF frequency (GHz)	PinLO (dBm)	Conversion Gain (dB)	ISO LO-RF (dB)	ISO LO-IF (dB)	IP1dB (dBm)	Туре	Status
CGY2180UH/C1	0.7-3.7	0.7-4	DC-2	15	-7	35	35	12	Die	Production
CGY2181UH/C1	1-4.5	1-5	DC-2	15	-7	45	32	13	Die	Production
CGY2182UH/C1	3-10	3-10	DC-3	15	-7	60	45	12	Die	Production
CGY2184UH/C1	0.1-6	0.1-6	DC-3	0	18	40	40	3	Die	Production
CGY2183UH/C1	0.1-6	0.1-6	DC-3	-5	12	35	40	-5	Die	Production
CGY2460UH/C1	40.5-43.5	8.8-10	5.0-6	9	33			0	Die	Production
CGY2470UH/C1	92-96	86-90	5.1-6	7	-3	4	3	2	Die	Production
CGY2471UH/C1	92-96	86-90	5.2-6	7	-10		>10	5	Die	Production

#### **Other products**



#### SPDT Switch:

CGY2370UH/C1 92 - 96 GHz

Isolation: 20 dB

Switching speed: 10 ns



#### SPDT Switch:

CGY2890SUH/C1

6-18 GHz

Isolation : > 50 dB Insertion Loss : 1.5 dB



#### Detector diode:

CGY2870AUH/C1

80-110 GHz

Zero bias

Input power : < 0 dBm

Input matching: -15 dB

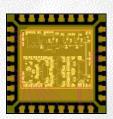


CGY2770UH/C2

11 - 11.5 to 88 - 92 GHz

Isolation: 20 dB

Output power: 5 dBm



T/R Chip (PA + LNA + SPDT)

GY2750H/C1

26 - 34 GHz

Gain (Rx & Tx): 20 dB Pout (Tx) : 35 dBm

NF (Rx): 3 dB

# Foundry Services III - V Processes

## **Epitaxy & Custom Wafers Processing**

D025PHS 250 nm GaAs pHEMT

ED02AH 180 nm E/D GaAs pHEMT

D01PH 135 nm GaAs pHEMT

D01MH 125 nm GaAs mHEMT

D007IH 70 nm GaAs mHEMT

DH15IB 1.5 µm InP HBT

D01GH 100 nm GaN/Si (or Sic) HEMT

D006GH 60 nm GaN/Si (or Sic) HEMT

## **Epitaxy**



OMMIC has a powerful R&D department developing its own processes starting from epitaxial structure. OMMIC has a number of MOCVD reactors and supply epi wafers in 3-, 4- and 6-inche

This activity includes pHEMT containing up to 25% indium in the GaInAs layer, as opposed to 40% that they use internally, as well as HBT structures.

#### Existing epi processes include:

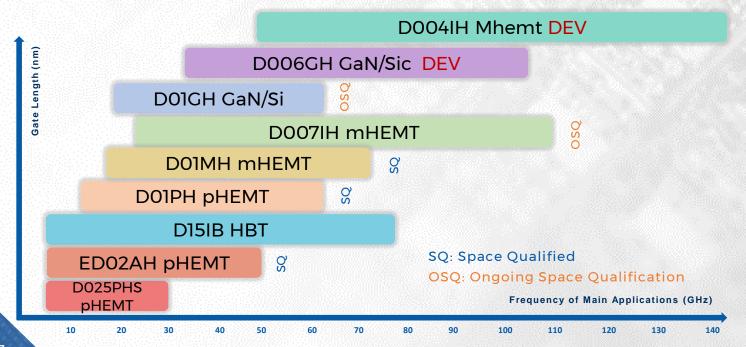
- GaAs MESFET and HFET
- GaAs and InP based PHEMT
- GaAs/GaInP HBT
- InP/GaAsSb HBT

pHEMT materials are provided with inline capless wafer data.

HBT materials are provided with inline wide area HBT test data.



### **Processes**



## **III-V Processes For Foundry Services**

You have not found any corresponding design in our standard product portfolio?

OMMIC as a fully open foundry policy, providing the most innovating processes to the rest of the world; use it to design the device that is best suited for you!

#### Processes & Technology

OMMIC is focused on III-V material for the performance it can offers. OMMIC process portfolio includes GaAs pHEMT & mHEMT technology, InP HBT technology and GaN HEMT technology. These services enable cut-off frequencies as high as 400 GHz enabling new application at always higher frequencies.

OMMIC processes are built for high reliability and space application. This is why all our processes in production are either spaced qualified by the European Space Agency, or in the process of being qualified.

#### **Low Noise Application**

All of OMMIC processes are designed to minimize the noise figure of the transistors.

Metamorphic technology (e.g D0071H, D004IH) is especially good for providing low noise at high frequencies.

Need for robust LNA (Pin > 40 dBm)? The large Breakdown voltage combined with the low noise of our GaN (DOIGH, DOOGGH) technologies makes it perfect for such feature.

#### **Power Application**

The well-trusted reliability of GaAs pHEMT (DOTPH) technology can be used for mid-power application in space. For other environment, take advantage of the high power density of our GaN processes (DOTGH, DOOGGH). OMMIC's GaN technology features high output power (up to W-band), but also high linearity, low noise and no noticeable memory effect.

#### Control Function

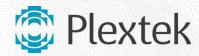
With our ED02AH process, it is possible to have enhanced (E) and depletion (D) transistors on the same die. Having E- and D-type transistors allows one to design control functions with a serial interface that simplifies the interaction with the device.

#### They are designing using OMMIC's PDK











## **GaN Processes**

OMMIC has released its first GaN process in 2015. All of the supply chain is located in Europe

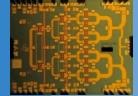
#### DOIGH

Process	D01GH
Technology	GaN on Si
Status	Pre-production
Space Grade	In 2020
Gate Length (μm)	0.1
Wafer Size (")	3
Thinkness (µm)	100
Gate Write	E-beam
Ft (GHz)	110
Fmax (GHz)	160
Vbgd (V)	36
Vds max (V)	12
Idss (mA/mm)	1200
Idss max (mA/mm)	1700
MIM Capacitors (pF/mm²)	400
NF (dB)	1.5 (40 GHz)
Power Density (mW/mm)	3300
gm (mS/mm)	800

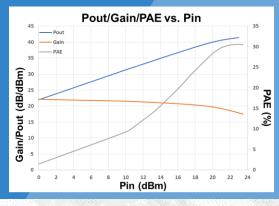
✓ Robust LNA ✓ Switch ✓ HPA

Well suited for application from 15 to 50 GHz

Representative Device: CGY2651UH



- ✓ Operating Range: 37 GHz to 43 GHz
- ✓ Gain: 18 dB
- ✓ Pout: 40 dBm @40 GHz
- ✓ PAE: 30 %
- ✓ Power Consumption:
  - $\checkmark$  V<sub>D</sub> = 12 V
  - $I_{Otot} = 0.84 A$



#### **D006GH**

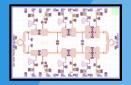
Process	D006GH
Technology	GaN on Si
Status	Development
Space Grade	-
Gate Length (μm)	0.06
Wafer Size (")	3
Thinkness (µm)	100
Gate Write	E-beam
Ft (GHz)	150
Fmax (GHz)	190
Vbgd (V)	36
Vds max (V)	12
ldss (mA/mm)	1200
ldss max (mA/mm)	1700
MIM Capacitors (pF/mm²)	400
NF (dB)	1 (40 GHz)
Power Density (mW/mm)	3300
gm (mS/mm)	900

✓ HPA

✓ Robust LNA ✓ Switch

Well suited for application from 50 to 100 GHz

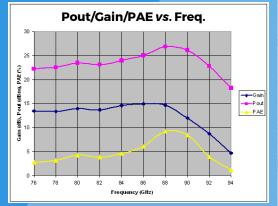
Development Device: Dev-WAVERIN



- ✓ Operating Range: 75 to 89 GHz, CW
- ✓ Gain: 14 dB
- ✓ Pout: 27 dBm @88 GHz
- ✓ PAE: 10 %

The process is currently being modified to increase the Ft

Pre-release at the end of the Year



## **GaAs m-HEMT Processes**

OMMIC has released metamorphic processes with up to 70 % of indium in the channel.

## D0071H

Process	D007IH	✓ LNA ✓ Mixer		
Technology	GaAs m-Hemt			
Status	Production	Well suited for application from <b>20</b> to <b>150 GHz</b>		
Space Grade	In 2020			
Gate Length (μm)	0.07			
Wafer Size (")	3	Representative Device : CGY2260UH/C1		
Thinkness (µm)	70    100			
Gate Write	E-beam	( On a wating a Day on 25 CHata ( 7 CHa		
Ft (GHz)	300	<ul> <li>✓ Operating Range: 25 GHz to 43 GHz</li> <li>✓ Gain: 25 dB (±0.4 dB on bandwidth)</li> <li>✓ NF 1.0 dB @36 GHz</li> </ul>		
Fmax (GHz)	450			
Vbgd (V)	4	✓ OP1dB: 8 dBm		
Vds max (V)	3	✓ Power Consumption:		
Idss (mA/mm)	200	$\sqrt{V_D} = 1.5 \text{ V}$ Noise Figure (dB)		
Idss max (mA/mm)	400	✓ I <sub>D</sub> = 0.52 A		
MIM Capacitors (pF/mm²)	400			
NF (dB)	0.5 (30 GHz)	1.5		
Power Density (mW/mm)	NA	0.5 0 25 27 29 31 33 35 37 39 41 Frequency (GHz)		
gm (mS/mm)	1600	· · · -quoisy (entry		

## **D0041H**

Process	D004IH	✓ LNA ✓ Mixer
Technology	GaAs m-Hemt	
Status	Development	Well suited for application from <b>60</b> to <b>250 GHz</b>
Space Grade	-	
Gate Length (µm)	0.04	
Wafer Size (")	3	The process is
Thinkness (µm)	100	currently <b>being modified</b>
Gate Write	E-beam	
Ft (GHz)	400	to <b>increase</b> the <b>Ft</b>
Fmax (GHz)	600	
Vbgd (V)	4	Pre-release at the end of the Year
Vds max (V)	3	
ldss (mA/mm)	200	
Idss max (mA/mm)	400	
MIM Capacitors (pF/mm²)	400	
NF (dB)	0.4 (30GHz)	
Power Density (mW/mm)	NA	
gm (mS/mm)	2000	20

## **GaAs p-HEMT Processes**

GaAs p-HEMT have been manufactured since the late nineties, whith a strong space heritage

#### DOIPH

Process	D01PH	✓ PA ✓ LNA ✓ Mixer ✓ TWA		
Technology	GaAs p-Hemt			
Status	Production	Well suited for application from <b>5</b> to <b>45 GHz</b> and		
Space Grade	<b>Space Qualified</b>	Space application		
Gate Length (μm)	0.135			
Wafer Size (")	3			
Thinkness (µm)	70    100	Representative Device : CGY2135UH/C1		
Gate Write	E-beam			
Ft (GHz)	100	✓ Operating Range: 18 GHz to 23 GHz		
Fmax (GHz)	180	✓ Gain: 25 dB ✓ OPldB: 31 dBm		
Vbgd (V)	12	✓ Power Consumption: 36 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1		
Vds max (V)	10	V - 4 V		
Idss (mA/mm)	500	$\checkmark I_D = 1.2 \text{ A}$		
Idss max (mA/mm)	700	E 28 28 26 26 28		
MIM Capacitors	400	(Eug) 26		
(pF/mm²)	400	22 20		
NF (dB)	1.1 (GHz)	18		
Power Density	640	16		
(mW/mm)	_	-10 -8 -6 -4 -2 0 2 4 6 8 10 12		
gm (mS/mm)	650	Pin(dBm)		

#### ED02AH

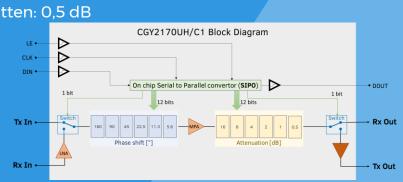
Process	ED02AH
Technology	GaAs p-Hemt
Status	Production
Space Grade	Space Qualified
Gate Length (μm)	0.18
Wafer Size (")	3
Thinkness (µm)	100
Gate Write	E-beam
Ft (GHz)	60
Fmax (GHz)	110
Vbgd (V)	8
Vds max (V)	7
Idss (mA/mm)	250(on)/140(off)
Idss max (mA/mm)	400(on)/180(off)
MIM Capacitors	
(pF/mm²)	49 & 400
NF (dB)	0.8 (18 GHz)
Power Density	
(mW/mm)	330
gm (mS/mm)	450

## ✓ Corechips ✓ LNA

Well suited for application from 1 to 40 GHz The E-&D-type transistors enables the implementation of digital functions

Representative Device: CGY2170UH/C1

- ✓ Operating Range: 8 GHz to 12GHz
- ✓ Gain: 5 dB
- ✓ RMS\_phase: 4 °
- ✓ RMS atten: 0,5 dB





# Design Center & Fab +

**Custom Design Services** 

Challenging Design from 5 to 200 GHz

ADS SPICE and AWR Design Kits

Multi Chip Projects Shared Wafer Service

Simulation & Extractions for Customers

System Modeling



## **Design Center & FAB+ Services**

Having trouble finding a product with exotic specification on the market? Check-out our other options:



## **Foundry Service**

## Custom Design

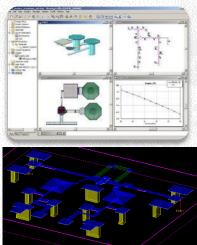


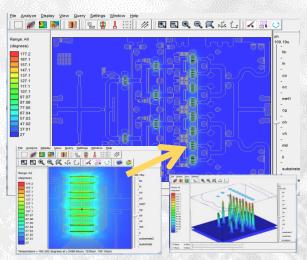
OMMIC provides its Process Design Kit (PDK) under ADS (preferred) or Microwave Office (AWR) for customers to design their own product. OMMIC provides custom design MMIC services based on customer's specifications, from DC to W-band.

Most of OMMIS's processes have completed or are running a Space evaluation (ESA-EPPL).

The OMMIC design Manuals and design tools are extremely comprehensive and allow any type of design. This includes mixed signal to low noise and high power, from DC to millimeter wave.







#### OMMIC Design Kits include:

- ✓ Fully scalable models for all devices
- ✓ Linear, non linear and noise models for transistors (and diodes)
- ✓ Process statistical variations of all active and passive devices, allowing representative yield analysis
- √Temperature effects for all passive and active devices
- √Complete auto layout for all devices, including all types of interconnections
- ✓ E.M. information allowing advanced analysis
- ✓ Electro-thermal simulator
- ✓ Design Rules Checking

Design kits are regularly updated, on our website in close collaboration with software suppliers. OMMIC provides hot line support, dedicated training, and powerful verification tools.

## **Design Center & FAB+ Services**

#### **Custom Design**

OMMIC design team is able to design MMICs from Customer specifications and Statement of Work.

- LNA
- Power Amplifiers
- · Multifunction chips including digital parts
- Multipliers
- Down-convertors or Trans Impedance Amplifiers from DC to W-band

The design flow includes several reviews where close discussions with the customer ensure that the final MMIC will really enhances the final system.

This design flow is based on space standards such as ECSS-Q60-12A and have been approved for flight model designs.

The Fabrication Line, Test Center, Reliability Center and Modeling Team are on the same site. This proximity allows OMMIC Design Center to obtain the best performances from all the OMMIC processes, while maintaining yield and reliability.

#### **Foundry service**



All of OMMIS's processes are available for full wafer foundry services. This service comes with on-wafer test (following customer specification) and visual inspection (MIL-STD-883). Before manufacturing, all projects are checked by OMMIC using the OMMIC design rule checker (DRC). DRCs are performed at no extra cost.

A MultiProject Wafer (MPW) is a cost effective way to experience a new design topology or a new technology through a limited number of samples. OMMIC has been offering this service for a long time on his proprietary technologies.

#### **Conditions of use**

- The size of the circuit must correspond to one of the fixed patterns for a MCP project.
- The Layout must be supplied according to a predefined time table available on the web site, by default 4 dates per year.
- MCP order should be placed at least 4 weeks before the announced MCP start date.
- The order needs to complain with minimum order value when it is applicable.

#### **University Partnership:**

OMMIC is committed to give access to its technologies for Educational Purposes to Universities and Educational Establishments. Please contact us for more details.

	Sizes	1.5 mm	3 mm
	1 mm	A = 1.5 mm <sup>2</sup> N = 25 Dies	A = 3 mm² N = 20 Dies
	2 mm	A = 3 mm <sup>2</sup> N = 20 Dies	A = 6 mm² N = 15 Dies
2 2 2 2 2 2 2 2 2 2 2 2 2 2 2 2 2 2 2 2		A : Area of the reticule N: Number of dies delivered	
		Other Die size can sometime be used, please contact OMMIC for special demands	

## **MPW Schedule**

#### **Space quafified:**

ED02AH

✓ 21 / 04 / 2018✓ 13 / 09 / 2018

D01PH

✓ 31 / 07 / 2018✓ 15 / 11 / 2018

D01MH

- × 31 / 07 / 2018
- √ 15 / 11 / 2018

## **High Indium content m-HEMT:**

D007IH

- ✓ 26 / 03 / 2018✓ 05/07 / 2018
- √ 15/10/2018

**D004IH** 

MPW dates not available yet

GaN:

D01GH

✓ 12 / 06 / 2018✓ 01 / 10 / 2018

D006GH

- 12/06/2018
- √ 01/10/2018

HBT:

**D15IB** 

√ 11 / 12 / 2018

For any other information or special request contact information@OMMIC.com

Visit our website http://www.ommic.com/site/mpw-4 for up-to-date information



More than 40 years in III - V industry

Produce on 3- and 6-inch wafers

Class 10,000 production clean room

Certified ISO9001 ISO14001&RoHs compliant Standard & Space grade visual inspection

On wafer test capabilities for microwave & mm-wave products

Competitive lead time & maximum flexibility



## **Production Line & Back-end**

OMMIC was founded on January 1, 2000 by Philips, based on a track record of 40 years of cutting -edge research and development in the fields of III-V epitaxy and integrated circuits technologies. Today, OMMIC is an independent SME.



OMMIC consists of 5 main buildings with 1 000 m<sup>2</sup> of clean rooms of class 1000 and class 100 which are fully devoted to III-V IC development and fabrication.

Our wafers are delivered with electrical properties guaranteed by the measurement of specific test modules added during the fabrication called PCM (Process Control Monitor).

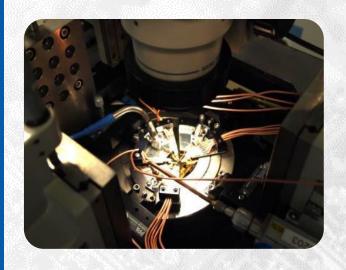
Our processes and our equipments are also followed with SPC (statistical process control).

Our on-wafer test center disposes of a wide variety of high performance tools and experienced people. It allows us to routinely measure the usual microwave characteristics like Sij, spectrum anal., Scalar meas., Noise figure, DC pulsed meas... All wafers are monitored by DC parametric and RF

All wafers are monitored by DC parametric and RF measurements during the Front End process.

Our experience in microwaves and mm-Waves tests and probe card's design, leads us to design complex tests procedures allowing testing the main performances and functionalities of our MMIC products in order to guarantee the delivery of known good dies.

We open to our customers our RF-test capabilities and knowledge to design and conduct tests on their own prototypes, in order to help them to validate and improve their products.





The visual inspection process plays an essential role in our manufacturing steps to ensure anomaly detection. We can therefore implement prompt corrective or preventive responses and verify the final quality of each die before sending them to our customers.

In order to do so, we perform preliminary visual inspections at each critical step in the production line with sampling and a final visual inspection.

All our products are inspected according to international standards (MIL-STD-883) by a trained and qualified inspection staff. Moreover, for products with less stringent requirements, a commercial grade die inspection is available.

## **Space Heritage** & Flight Models

## **Services & Tools**

**Custom Design Services** 

Challenging Design from 5 to 200 GHz

ADS SPICE and AWR Design Kits

Multi Chip Projects Shared Wafer Service

Simulation & Extractions for Customers

**System Modeling** 



## **Space Heritage**

More than 30 000 MMICs have been supplied for Flight Models. OMMIC has more than 100 000 years of accumulated Flight Life time around earth in several space mission and satellite equipment.



Components from OMMIC have been used in Flight Models for satellites from Europe, USA, India, Russia and other countries.

#### Functions include:

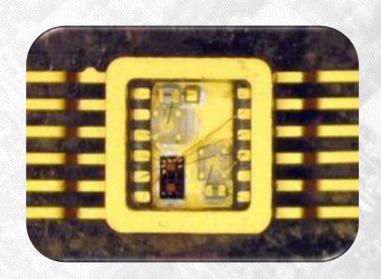
- Frequency Converters components as mixers and modulators
- Linear Components as Low Level Amplifiers, LNAs.
- Control Components as Phase Shifters, Attenuators.
- Power Components such as Medium Power Amplifiers.
- Non Linear Components such as Frequencies Multipliers.
- Negative Resistor for Oscillators.
- Multi-functions components composed by several functions.
- Numerical Components as Phase or Frequency Detector.

ESA has already evaluated 3 OMMIC processes ED02AH, D01PH and D01MH, these 3 processes being maintained on ESA EPPL list.

2 additional processes are considered to be inserted in the EPPL list after ESA monitored evaluation procedures.

OMMIC has already delivered many standard parts designed during the ECI (European Component Initiative) programs.

OMMIC can be a custom design center for space qualified components, many of them have already been designed by OMMIC's design team.



## They have already trusted **OMMIC**





Together ahead. RUAG









## **Space Qualification & Reliability Center**

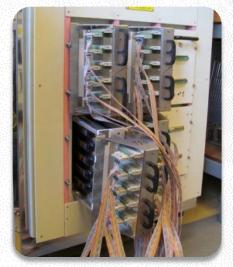
OMMIC has a dedicated team for space qualification of flight models but also for reliability of all our components.

#### **Test performed for SPACE EVALUATION FLOW of Flight Model MMICs**

All tests below are **Assembly test** for flight models and are performed at OMMIC in our reliability laboratory



We also perform Aging and life cycle tests when requested like in MIL-STD-883 standard





**High temperature DC life test** 

**Room temperature RF stress test** 

## **Space Qualification & Reliability Center**

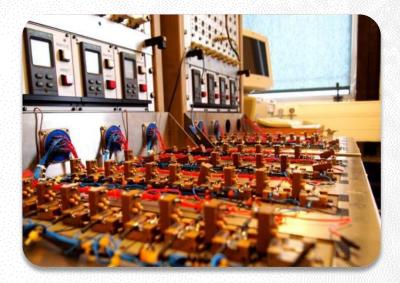
OMMIC has a dedicated team for space qualification of flight models, but also for reliability of all our components.

· Die-shear (MIL-STD-883G,method 2011.7) - 2 samples/batch · Bond-pull (MIL-STD-883G,method 2019.7 z) - 2 samples/ batch · Pre-cap inspection (SCC 20400) **Packaged Chips** · Hermeticity test QUALIFICATION FLOW · OMMIC specification ·12 chips by wafer all kinds of considered MMIC **Initial electrical** measurements ·100% of MMIC · MIL STD 883 method 1015 **Burn-in test** ·160h @ 125°C (oven temperature) · OMMIC specification Final electrical measurements & External visual inspection · Hermeticity test

**Delivered** 

LAT

- Temperature cycling (MIL-STD-883G / 1010 cond. C)
- Constant Acceleration (MIL-STD-883G / 2001 cond. E, Y1 axis only)
- · Electrical measurements (-20°C, room temperature, +80°C)



Aging biasing test bench



**Burn-in Tests ovens** 



5G LTE

Global & dedicated customer support

System studies support

On field demonstration upon request

Mounting support

Packaging support

Custom modules design studies

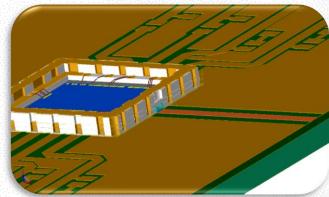


## **MMIC Packaging**

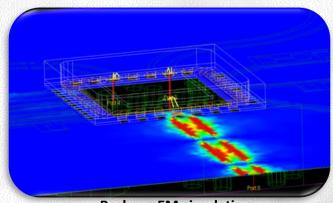
We are moving towards a world where integration and ease of use are central to the definition of complex electronic subsystems.

OMMIC invests every day to simplify the use of its products for its customers by developing packaged solutions while ensuring optimal performances.

#### **Exemple of modeling with EM simulation:**



Package physical model



Package EM simulation

Today, our solutions cover L-, S-, C- and X-band. Following our customers request, we are now focusing on packaging our Ka-band corechips solutions.

#### **Exemple of LNA and Corechip packaged solution:**

CGY2221HV/C1



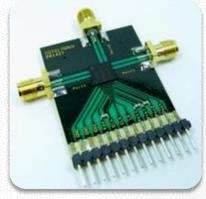
LNA 7.5 - 13 GHz NF: 1.6 dB Plastic QFN 4x4

CGY2392SHV/C1



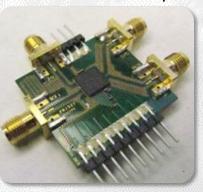
Phase-Shifter 7.5 - 13 GHz RMS Phase Error 1.7 ° @ 12 GHz Plastic QFN 5x5

CGY2175AHV



6 bit C-band Corechip
Plastic QFN 7x7

**Custom Ku-band Corechip** 



4 ports
Plastic QFN 7x7

## **Sales Support & Application**

Based in France, in Paris area, OMMIC occupies a central position in Europe, but also in the world, to deliver the right product in the right time to customers. Thanks to its powerful supply chain and reactive regional reps network, OMMIC can support any project in the entire world.



#### Sales Representative Network

#### Eastern U.S.A

GM Systems LLC terlizzi@gmsystems.com

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Rankin Components Sales trankin@rankincomponents.com

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American Aviation yoav@amav.co.il

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A sales and field application team at OMMIC is dedicated to customer sales and technical request to provide the best support in the shortest time.

Due to its world class status and human size, OMMIC is a very flexible company able to follow you in your most challenging projects.

You can contact our support team whenever you need at *information@ommic.com* Or meet us at international RF events such as IMS or EuMW.

# **OMMIC**

**Short Form Catalog 2018** 

**GM** SYSTEMS

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